

Filter Improves Liquid Filtration Performance in Semiconductor Manufacturing

The new family of 20nm- to 100nm-rated cartridge filters for chemicals, dilutes chemicals, and ultrapures water in wet process tools. This incorporates a new high-flow ePTFE (expanded polytetrafluoroethylene) filtration media that allows a drop-in retention upgrade from 100nm to 30nm, enabling cleaner recirculation baths, reduced processing times, and significant savings in cost of ownership. The new cartridge filters enable up to three times the flow compared to the next best-in-class filters, with improved performance and no sacrifice in retention. The filter also provides a drop-in replacement that improves retention performance, reduces particle counts, lowers operating differential pressures, reduces processing times, and enables faster bath turnovers.

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